

**Course: Semiconductor Device Fundamentals**

**Level: Undergraduate**

**Module: C**

**Test: C18**

**Type: Closed Book, Closed Notes**

**Note: Available Info/Equation Sheets**

**Problem Weighting---**

- F-1...32 (4 each part)**
- F-2...28 (4 each part)**
- F-3...24 (4 each part)**
- F-4...16**

F - 1

Using the energy band diagram indicate how you would visualize...

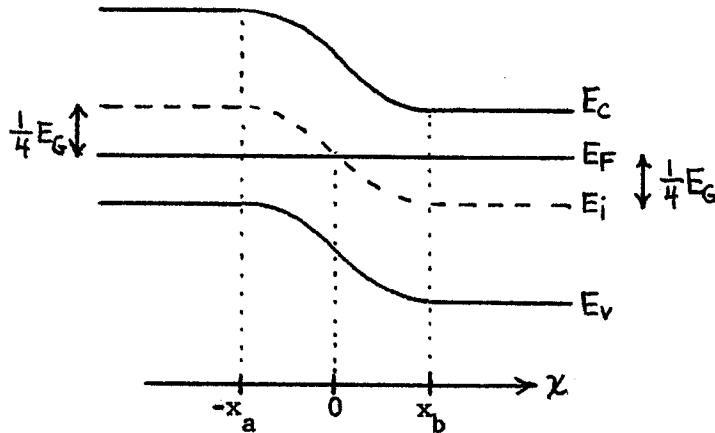
- (a) Freeze-out of majority carrier electrons at donor sites as the temperature is lowered toward 0°K.
- (b) Capture of a conduction band electron at a Recombination-Generation site.
- (c) Avalanching in a PN junction diode.
- (d) A PNP Bipolar Junction Transistor (BJT) under active mode biasing. (Please label the emitter, base and collector regions E, B and C respectively.)
- (e) Interfacial traps in an MOS structure.

Sketch an outline of the depletion region(s) in...

- (f) a  $P^+NP^-$  Bipolar Junction Transistor under active mode biasing.
- (g) an n-channel J-FET where  $V_P < V_G < 0$  and  $0 < V_D < V_{Dsat}$ .
- (h) an n-channel MOSFET biased at the pinch-off point ( $V_D = V_{Dsat}$ ).  
---Also include the inversion layer in this sketch.

F - 2

The energy band diagram shown in Fig. PF-2 characterizes a junction diode maintained at room temperature. Answer the questions which follow using the information conveyed in the diagram and the data adjacent to the diagram.



<u>Data</u>
$kT = 0.0255\text{eV}$
$E_G = 1.43\text{eV}$
$K_S = 10.9$
$\epsilon_o = 8.85 \times 10^{-14} \text{ f/cm}$
$A(\text{area}) = 10^{-2} \text{ cm}^2$
$x_a + x_b = 10^{-3} \text{ cm}$

Fig. PF-2

- (a) Assuming a uniform  $N_A$  doping for  $x < 0$  and a uniform  $N_D$  doping for  $x > 0$ , is the semiconductor degenerate at any point? Explain.
- (b) Sketch the electrostatic potential ( $V$ ) inside the diode as a function of  $x$ .
- (c) Sketch the electric field ( $\mathcal{E}$ ) inside the device as a function of  $x$ .
- (d) What is the voltage ( $V_A$ ) being applied to the device? Explain how you arrived at your answer.
- (e) Determine  $V_{bi}$ , the built-in voltage. (A numerical answer is required--and you must show how you obtained it.)
- (f) Approximately, what will be the junction (or depletion layer) capacitance exhibited by the diode at the pictured bias point?
- (g) In the given device is junction breakdown expected to be caused by avalanching or the Zener process? Explain.

F - 3

The d.c. state of an MOS-Capacitor is characterized by the block charge diagram shown in Fig. PF-3. Answer the questions below making use of the information conveyed in the diagram.

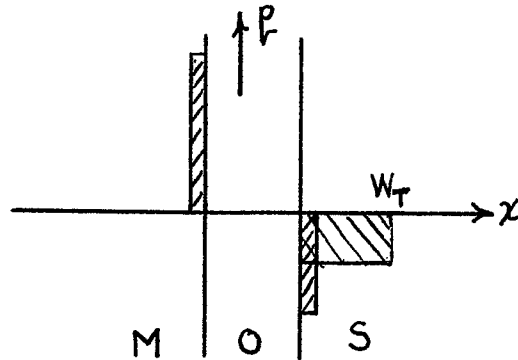


Fig. PF-3

- (a) Is the semiconductor N or P-type? Explain.
- (b) Is the device accumulation, depletion, or inversion biased? Explain.
- (c) Assuming the MOS-C is ideal, draw the energy band diagram corresponding to the charge state pictured in the block charge diagram.
- (d) By appropriately modifying the block charge diagram, indicate how the charge state inside the MOS-C is modified when a small-signal high-frequency a.c. signal is applied to the structure.
- (e) Sketch the general shape of the high-frequency C-V characteristic to be expected from the structure and indicate by a  $\odot$  the operating point corresponding to the Fig. PF-3 block charge diagram.
- (f) Suppose the MOS-C is biased at the same gate voltage giving rise to the Fig. PF-3 diagram, but is totally deep depleted. Draw the block charge diagram describing the new state of the system.

F - 4

Through ion-implanation it is now possible to effectively create a negative fixed charge (call this new charge  $Q_I$ ) at the Si-SiO<sub>2</sub> interface. With this  $Q_I$  one can cancel out the effects of  $Q_F$ ,  $\phi_{MS}$ , etc. and successfully build MOSFET's with  $V_G = 0$  turn-on voltages.

GIVEN...

(1) Al - SiO<sub>2</sub> - Si structure ( $\bar{\Phi}'_M - \chi' = -0.11\text{eV}$ )

(2)  $N_D = 10^{15}/\text{cm}^3 = \text{Si substrate doping}$

(3)  $V'_T = -1.39\text{V}$  ( $V'_T = \text{ideal device turn-on voltage}$ )

(4) No interfacial traps

(5) No mobile ions in the oxide

(6)  $Q_F/q = 2 \times 10^{11}/\text{cm}^2$  (This is the normal positive fixed charge.)

(7)  $x_o = 0.2\mu = 2 \times 10^{-5}\text{cm}$

(8) Room temperature operation where  $kT/q = 0.0255\text{V}$ ,  $E_G = 1.12\text{eV}$  and  $n_i = 8.6 \times 10^9/\text{cm}^3$ . Also,  $K_O = 3.9$  and  $\epsilon_o = 8.85 \times 10^{-14}\text{f/cm}$

DETERMINE the ions/cm<sup>2</sup> ( $-Q_I/q$ ) required to achieve a  $V_G = 0$  turn-on voltage.

NOTE: As established in the text,

$$\Delta V_G = (V_G - V'_G)|_{\text{same } U_S} = -\frac{Q_M \bar{y}_M}{C_o} - \frac{Q_F}{C_o} - \frac{Q_{IT}(U_S)}{C_o} + \phi_{MS} \quad \leftarrow \text{DOES NOT INCLUDE } Q_I$$

$$\text{where } \bar{y}_M \equiv \frac{\int_0^{x_o} x \rho_{ox}(x) dx}{x_o \int_0^{x_o} \rho_{ox}(x) dx}$$

$$\text{and } C_o = \frac{K_O \epsilon_o}{x_o}$$

$$\phi_{MS} = \frac{1}{q} \left[ \bar{\Phi}'_M - \chi' - (E_C - E_F)_\infty \right]$$